

Title (en)
DEVICE AND METHOD FOR CLEANING AND DRYING OBJECTS USED TO PRODUCE SEMICONDUCTORS, ESPECIALLY TRANSPORT AND CLEANING CONTAINERS FOR WAFERS

Title (de)
VORRICHTUNG UND VERFAHREN ZUM REINIGEN UND TROCKNEN VON BEI DER HERSTELLUNG VON HALBLEITERN VERWENDETEN GEGENSTÄNDEN, INSBESONDERE VON TRANSPORT- UND REINIGUNGSBEHÄLTERN FÜR WAFER

Title (fr)
DISPOSITIF ET PROCEDE DE NETTOYAGE ET DE SECHAGE D'OBJETS UTILISES AU COURS DE LA FABRICATION DE SEMICONDUCTEURS, EN PARTICULIER, DE RECIPIENTS DE TRANSPORT ET DE NETTOYAGE POUR PLAQUETTES

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Abstract (en)
[origin: WO2005001888A2] The invention relates to a device and a method for cleaning objects used to produce semiconductors, especially transport and cleaning containers for wafers, LCD substrates and photomasks. Said objects are cleaned in a treatment chamber (40) by means of a liquid, and are then dried. Means for circulating a gas inside the treatment chamber (40) and a condensation drier (64) for the gas are provided in the treatment chamber (40).

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